Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Withdrawn - Currently Amended) A substrate inspection system comprising:

a first inspection apparatus executing a macro inspection of each of a plurality
of substrates and outputting information on presence/absence of a defect on each of the
substrates:

a storage unit storing therein for each of the substrates the information on presence/absence of a defect outputted from said first inspection apparatus; and

a second inspection apparatus executing to execute an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

said second inspection apparatus refers to the information on presence/absence of a defect stored in said storage unit and executes the inspection of substrate(s) of substrates from amongst the plurality of substrates, the substrate(s) being one(s) that does/do not based on whether or not the substrates have the defect.

- 2. (Withdrawn) The substrate inspection system according to claim 1, wherein said second inspection apparatus executes the inspection by measuring a relative offset between a resist pattern formed on a surface of the substrate and an underlying pattern.
- 3. (Withdrawn Currently Amended) A substrate inspection system comprising:

 a first inspection apparatus executing a macro inspection of each of a plurality
 of substrates and outputting information on distribution of a defect on each of the substrates;

 a storage unit storing therein for each of the substrates the information on
 distribution of a defect outputted from said first inspection apparatus; and

a second inspection apparatus executing to execute an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

said second inspection apparatus refers to the information on distribution of a defect stored in said storage unit and executes the inspection of substrate(s) of substrates from amongst the plurality of substrates, the substrate(s) being one(s) that does/do not based on whether or not the substrates have the defect distributed in the predetermined portion.

- 4. (Withdrawn) The substrate inspection system according to claim 3, wherein said second inspection apparatus executes the inspection by measuring a relative offset between a resist pattern formed on a surface of the substrate and an underlying pattern.
- 5. (Withdrawn Currently Amended) A substrate inspection system comprising: a first inspection apparatus executing a macro inspection of each of a plurality of substrates and outputting information on distribution and classification of a defect on each of the substrates;

a storage unit storing therein for each of the substrates the information on distribution and classification of a defect outputted from said first inspection apparatus; and a second inspection apparatus executing to execute an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

said second inspection apparatus refers to the information on distribution and classification of a defect stored in said storage unit and determines substrate(s) to be inspected to determine which of the substrates from amongst the plurality of substrates are to be inspected by the second inspection apparatus.

6. (Withdrawn - Currently Amended) The substrate inspection system according to claim 5, wherein

said second inspection apparatus determines substrate(s) which of the substrates are to be inspected according to how much a kind of the defect contained in the classification information is associated with a kind of a defect detectable by said second inspection apparatus.

- 7. (Withdrawn) The substrate inspection system according to claim 5, wherein said second inspection apparatus executes the inspection by measuring a line width of a resist pattern formed on a surface of the substrate.
- 8. (Withdrawn Currently Amended) A substrate inspection method comprising:
 a first inspection step of executing a macro inspection of each of a plurality of
 substrates and outputting information on presence/absence of a defect on each of the
 substrates;

a storage step of storing for each of the substrates the information on presence/absence of a defect outputted in said first inspection step; and

a second inspection step of executing an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

in the second inspection step, the information on presence/absence of a defect stored in said storage step is referred to, and the inspection is executed on substrate(s) of substrates from amongst the plurality of substrates, the substrate(s) being one(s) that does/do not based on whether or not the substrates have the defect.

9. (Withdrawn) The substrate inspection method according to claim 8, wherein

in the second inspection step, the inspection is executed by measuring a relative offset between a resist pattern formed on a surface of the substrate and an underlying pattern.

10. (Withdrawn - Currently Amended) A substrate inspection method comprising:
a first inspection step of executing a macro inspection of each of a plurality of
substrates and outputting information on distribution of a defect on each of the substrates;
a storage step of storing for each of the substrates the information on
distribution of a defect outputted in said first inspection step; and

a second inspection step of executing an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

in the second inspection step, the information on distribution of a defect stored in the storage step is referred to, and the inspection is executed on substrates from amongst the plurality of substrates, the substrates being one(s) that does/do not based on whether or not the substrates have the defect distributed in the predetermined portion.

- 11. (Withdrawn) The substrate inspection method according to claim 10, wherein in the second inspection step, the inspection is executed by measuring a relative offset between a resist pattern formed on a surface of the substrate and an underlying pattern.
- 12. (Withdrawn Currently Amended) A substrate inspection method comprising:
 a first inspection step of executing a macro inspection of each of a plurality of
 substrates and outputting information on distribution and classification of a defect on each of
 the substrates;

a storage step of storing for each of the substrates the information on distribution and classification of a defect outputted in said first inspection step; and

a second inspection step of executing an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

in the second inspection step, the information on distribution and classification of a defect stored in said storage step is referred to, and substrate(s) to be inspected is/are determined in order to determine which of the substrates from amongst the plurality of substrates are to be inspected by the second inspection step.

13. (Withdrawn - Currently Amended) The substrate inspection method according to claim 12, wherein

in the second inspection step, substrate(s) which of the substrates to be inspected is/are are determined from the plurality of substrates according to how much a kind of the defect contained in the classification information is associated with a kind of a defect detectable in the second inspection step.

- 14. (Withdrawn) The substrate inspection method according to claim 12, wherein in the second inspection step, the inspection is executed by measuring a line width of a resist pattern formed on a surface of the substrate.
- 15. (Withdrawn Currently Amended) A substrate inspection apparatus comprising:

a storage unit storing therein information on presence/absence of a defect on each of a plurality of substrates, the information being obtained as a result of a macro inspection of each of the substrates; and

an inspection section executing to execute an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

said inspection section executes the inspection of substrate(s) of substrates

from amongst the plurality of substrates based on the information on presence/absence of a defect stored in said storage unit, the substrate(s) being one(s) that does/do not substrates

being inspected based on whether or not the substrates have the defect.

16. (Withdrawn - Currently Amended) A substrate inspection apparatus comprising:

a storage unit storing therein information on distribution of a defect on each of a plurality of substrates, the information being obtained as a result of a macro inspection of each of the substrates; and

an inspection section executing to execute an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

said inspection section executes the inspection of substrate(s) of substrates

from amongst the plurality of substrates based on the information on distribution of a defect
stored in said storage unit, the substrate(s) being one(s) that does/do not substrates being
inspected based on whether or not the substrates have the defect distributed in the
predetermined portion.

17. (Withdrawn - Currently Amended) A substrate inspection apparatus comprising:

a storage unit storing therein information on distribution and classification of a defect on each of a plurality of substrates, the information being obtained as a result of a macro inspection of each of the substrates; and

an inspection section executing to execute an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

said inspection section determines-substrate(s) which of the substrates are to be inspected from the plurality of substrates based on the information on distribution and classification of the defect stored in said storage unit.

18. (Withdrawn - Currently Amended) A substrate inspection method comprising:
a first inspection step of executing a macro inspection of each of a plurality of
substrates and outputting information on a defect on each of the substrates;

a storage step of storing for each of the substrates the information on a defect outputted in said first inspection step; and

a second inspection step of executing an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

in the second inspection step, the substrate(s) and/or region(s) thereof to be inspected is/are determined substrates or the regions of the substrates from amongst the plurality of substrates while that are to be inspected are determined by referring to the information on a defect stored in the storage step, the regions including the predetermined portion of the substrates.

19. (Withdrawn - Currently Amended) The substrate inspection method according to claim 18, wherein:

the information on the defect obtained in the first inspection step is information on presence/absence of a defect on each of the substrates, and

on the regions thereof that does/do not of the substrates based on whether or not the substrates or or regions have the defect.

20. (Withdrawn - Currently Amended) The substrate inspection method according to claim 18, wherein:

the information on the defect obtained in the first inspection step is information on distribution of the defect on each of the substrates, and

the second inspection step is executed on the substrate(s) and/or substrates or on the regions thereof that does/do not of the substrates based on whether or not the substrates or regions have the defect distributed in-a the predetermined portion of the substrate.

21. (Withdrawn - Currently Amended) The substrate inspection method according to claim 18, wherein:

the information on the defect obtained in the first inspection step is information on distribution and classification of the defect on each of the substrates, and the second inspection step is executed on the substrate(s) and/or substrates or on the regions thereof of the substrates based on the stored distribution and classification of the defect for each of the substrate substrates.

- 22. (Currently Amended) A substrate inspection system comprising:

 a first inspection apparatus executing a macro inspection of each of a plurality
 of substrates and outputting information on a defect on each of the substrates;
- a storage unit storing therein for each of the substrates the information on a defect outputted from said first inspection apparatus; and
- a second inspection apparatus executing to execute an inspection of a predetermined portion of the substrate substrates, the predetermined portion set in advance of the macro inspection, wherein

said second inspection apparatus refers to the information on a defect stored in said storage unit and determines substrate(s) and/or regions thereof which of the substrates or which regions of the substrates are to be inspected from amongst the plurality of substrates, the regions including the predetermined portion of the substrates.

23. (Currently Amended) The substrate inspection system according to claim 22, wherein:

the information on the defect obtained by the first inspection apparatus is information on presence/absence of a defect on each of the substrates, and

the second inspection apparatus refers to the information on presence/absence of a defect and executes the inspection of the substrate(s) and/or substrates or of the regions thereof that does/do not of the substrates based on whether or not the substrates or the regions have the defect.

24. (Currently Amended) The substrate inspection system according to claim 22, wherein:

the information on the defect obtained by the first inspection apparatus is information on distribution of the defect on each of the substrates, and

the second inspection apparatus refers to the information on distribution of a defect and executes the inspection of the substrate(s) and/or substrates or of the regions thereof that does/do not of the substrates based on whether or not the substrates or regions have the defect distributed in-a the predetermined portion of the substrate substrates.

25. (Currently Amended) The substrate inspection system according to claim 22, wherein:

the information on the defect obtained by the first inspection apparatus is information on distribution and classification of the defect on each of the substrates, and the second inspection apparatus refers to the information on distribution and

classification of the defect and executes the inspection of the substrate(s) and/or substrates or of the regions-thereof of the substrates based on the stored distribution and classification of the defect for each of the substrate substrates.

26. (Previously Presented) The substrate inspection system according to claim 22, wherein:

said second inspection apparatus executes the inspection by measuring a relative offset between a resist pattern formed on a surface of the substrate and an underlying pattern.

27. (Previously Presented) The substrate inspection system according to claim 22, wherein:

said second inspection apparatus executes the inspection by measuring a line width of a resist pattern formed on a surface of the substrate.